

Acknowledgments

We acknowledge the James Watt Nanofabrication Centre at Glasgow University for carrying out the electron beam lithography. The fabrication was carried out in the framework of NanoPix (www.nanophotonics.eu). We acknowledge L.C. Andreani for helpful discussions. The research was supported under the European contract SPLASH of the 6th EU Framework Program and through the EPSRC UK Silicon Photonics Project. M. Spasenović acknowledges the support of the EC under the Marie Curie Scheme (contract number MEST-CT-2002-021000). This work is part of the research program of FOM, which is financially supported by NWO. L. O'Faolain, S. A. Schulz, and D. M. Beggs contributed equally to this paper.